
Properties of silicon and coatings for a low-temperature detector

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J. Degallaix, V. Dolique, R. Flaminio, D. Forest

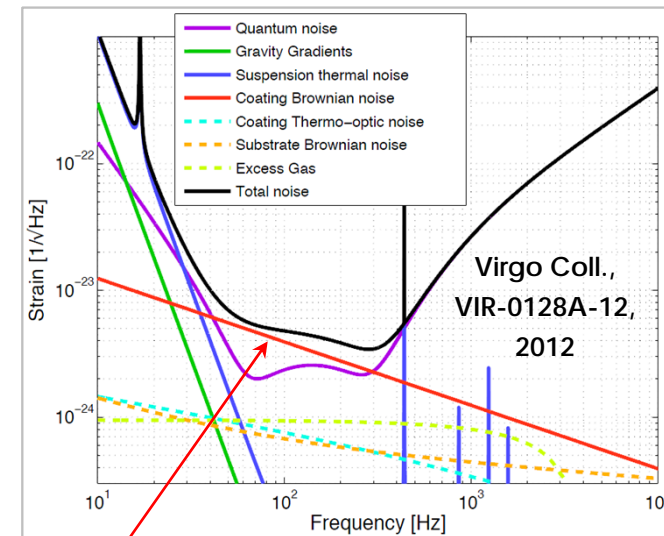
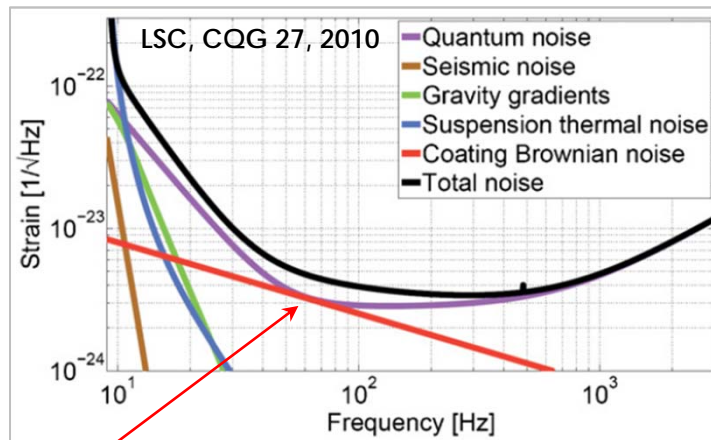
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Outline

- Introduction
- Experimental setups
- Results
- Summary and conclusions

Motivation

future gravitational-wave (GW) interferometers will be limited by coating thermal noise

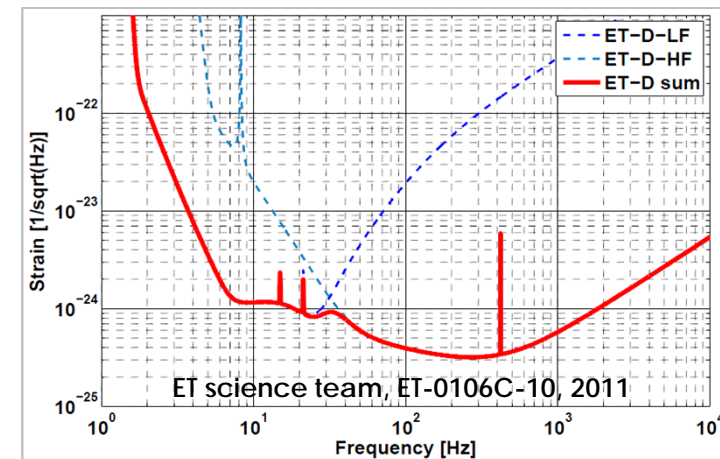


a solution: cryogenic GW detectors → R&D on substrates and coatings

→ low-temperature characterization of

- substrate optical absorption $\alpha(T)$
- coating mechanical loss $\Phi_c(T)$

→ best cryogenic resonators



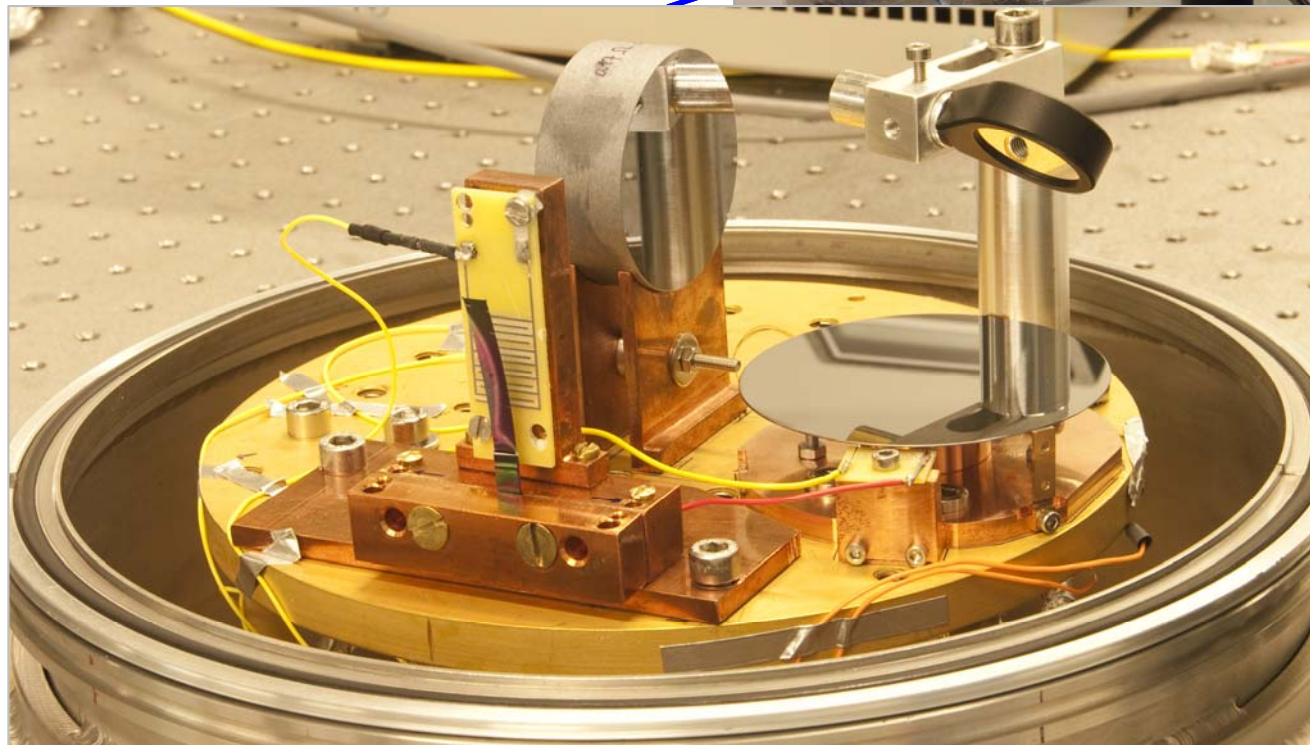
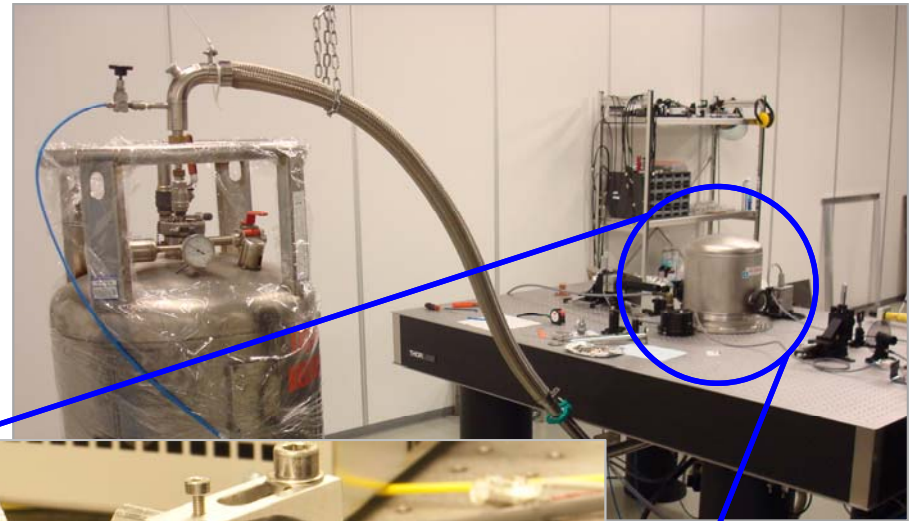
Experimental setup

continuous-flow cryostat:

- liquid He, $T < 10$ K

3 experiments:

- substrate absorption
- coating loss: disks [GeNS]
cantilever blades

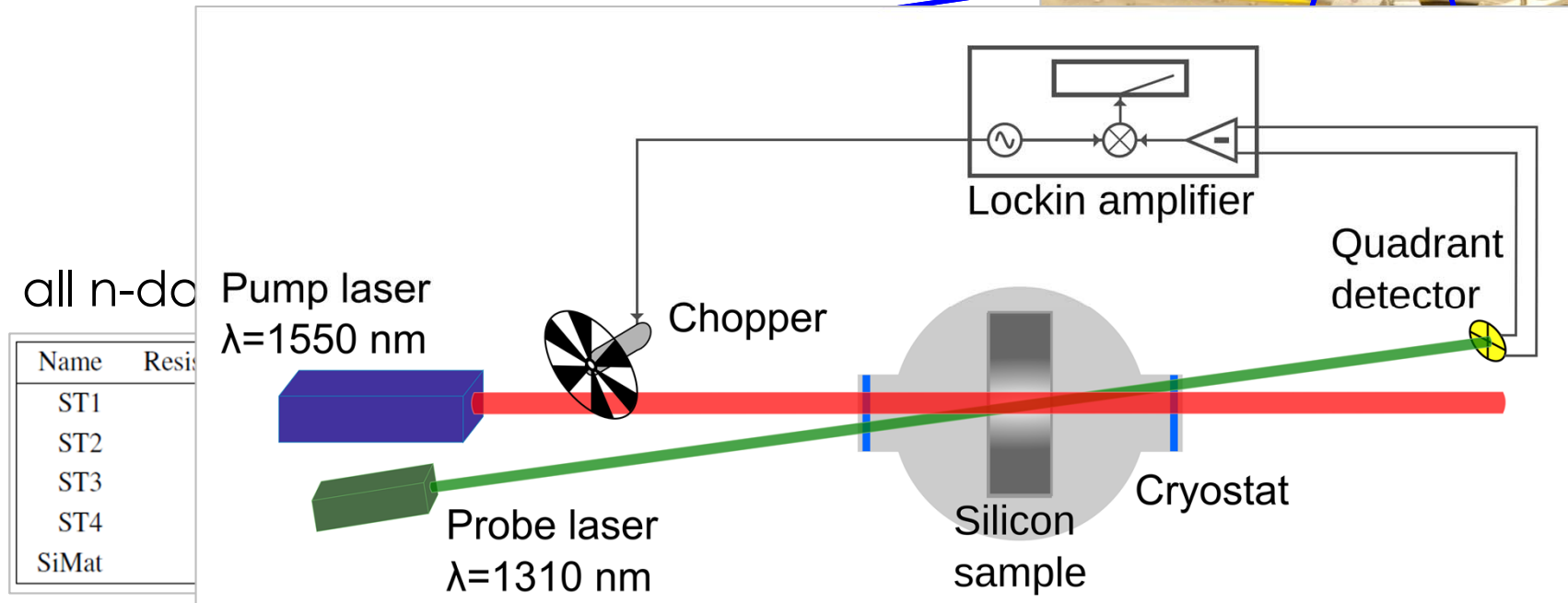


Substrate optical absorption

[see also previous talk by J. Komma]

Measurements

photo-deflection ('*mirage*') technique:



pump laser absorption

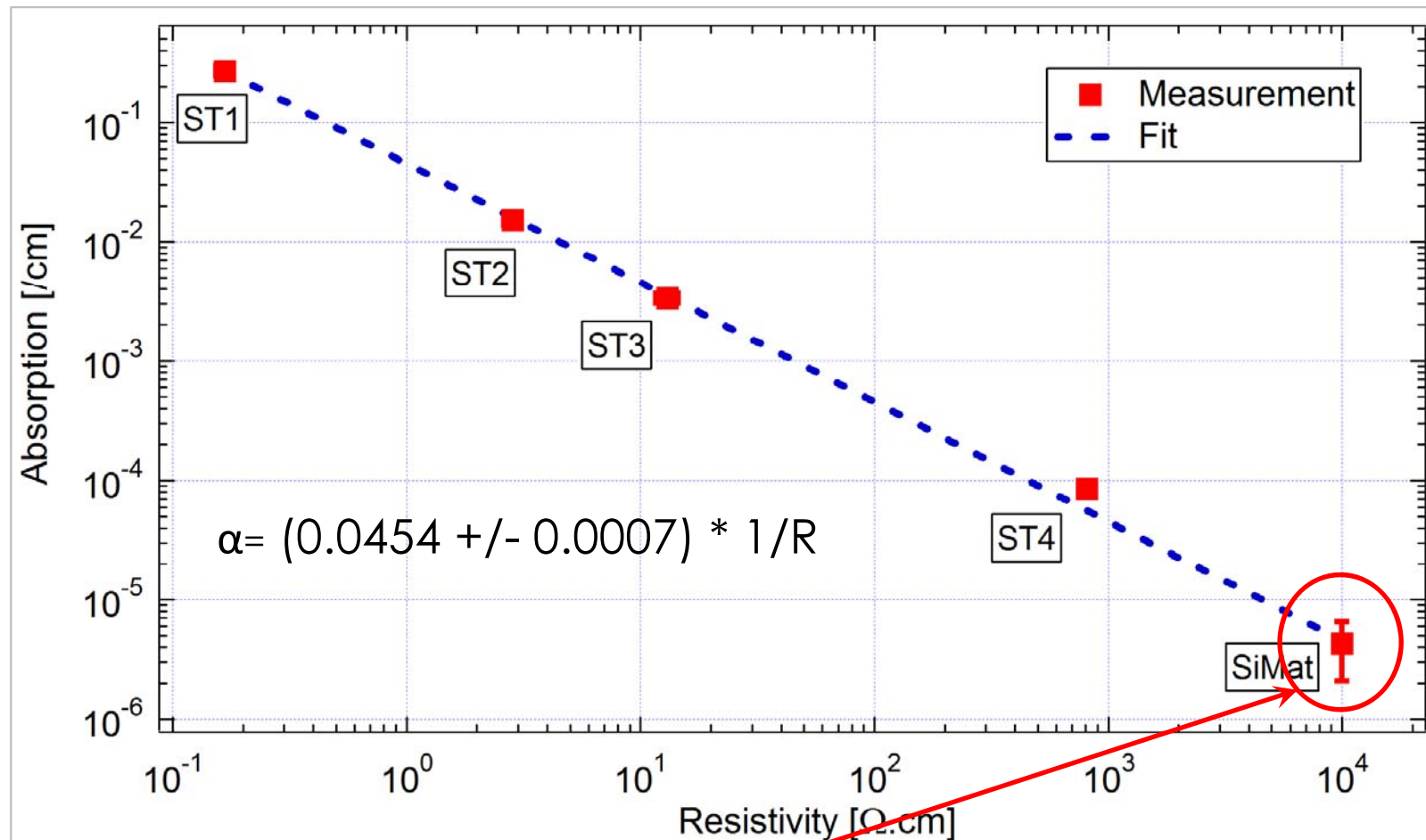
→ gradient of temperature

→ gradient of refractive index $n(T)$

→ probe laser deflection

very accurate but indirect measurement → calibration → ppm/cm

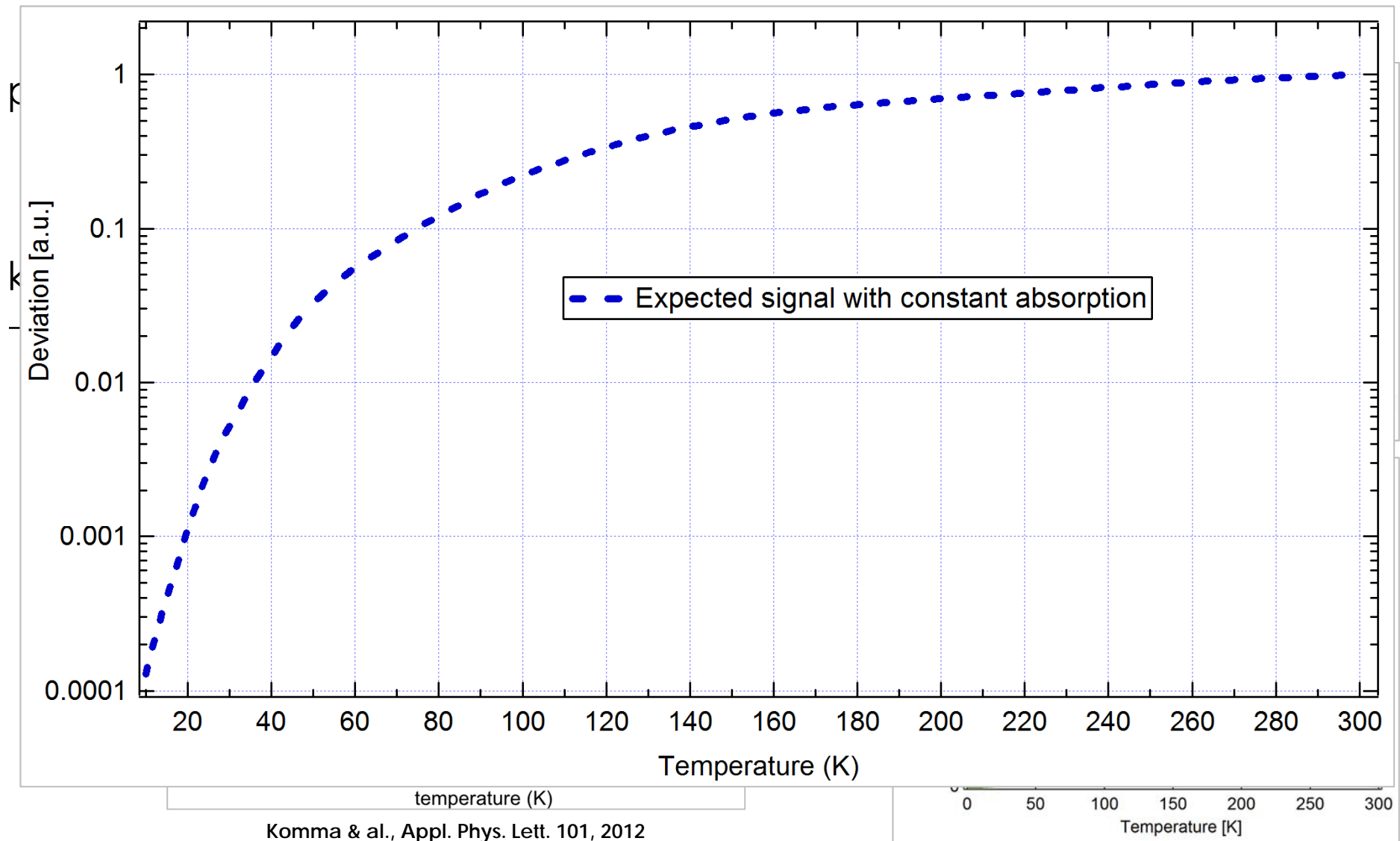
Room-temperature results



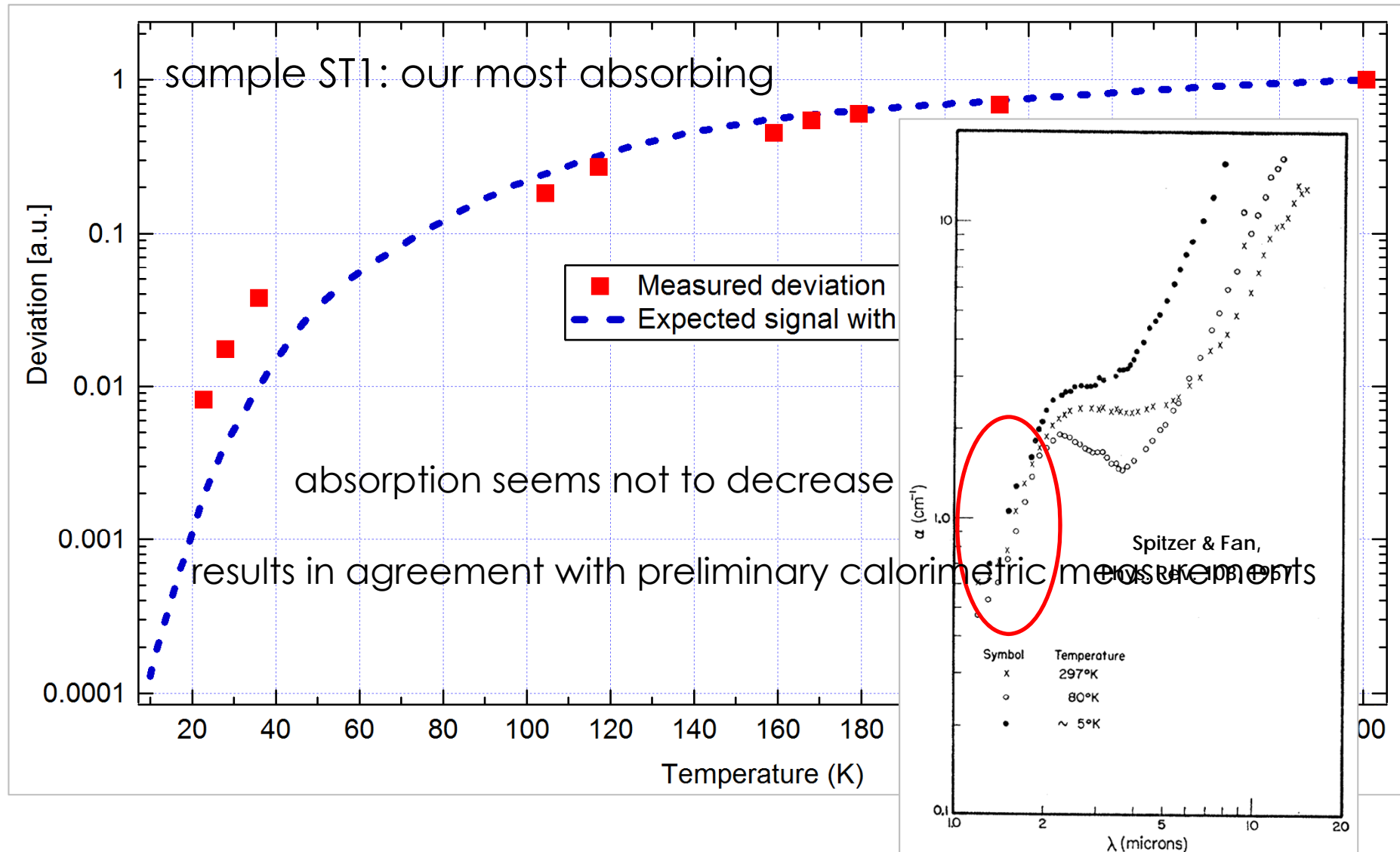
$\alpha = 4.3 \text{ ppm/cm}$: lowest Si absorption measured so far

more details: J. Degallaix & al., accepted for publication on Optics Letters

Low temperature - theory



Low-temperature results



Coating mechanical loss

– disks –

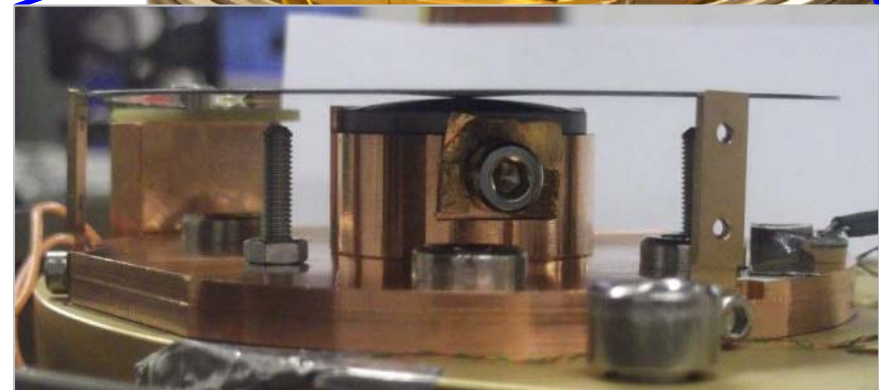
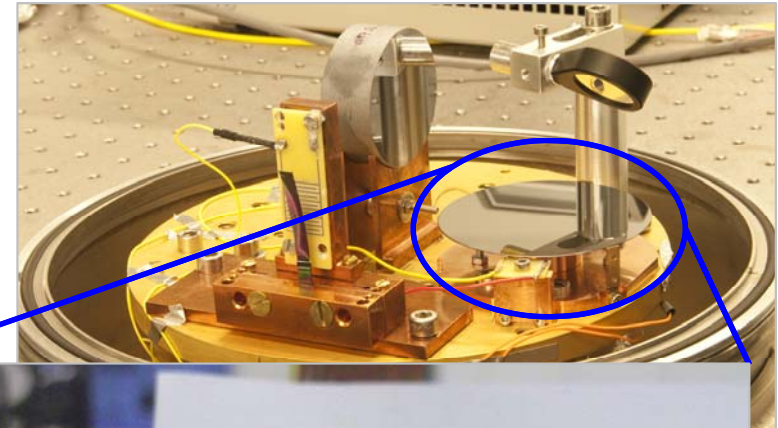
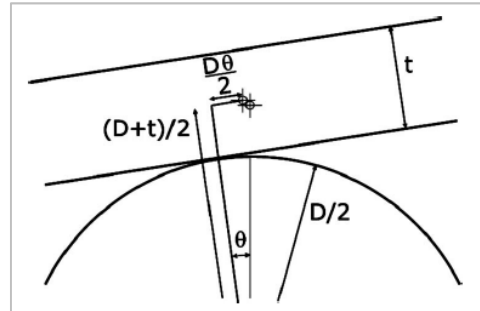
[see also R. Flaminio's talk of last wednesday]

Gentle Nodal Suspension – GeNS

system developed in Florence for Q measurements on thin disks

Cesarini & al., Rev. Sci.
Instrum. 80, 2009

Cesarini & al., Class.
Quantum Grav. 27, 2010



1"-silicon lens, 63mm radius of curvature
3"-diameter, 460 μ m-thick silicon disk
contact point position accuracy < 10 μ m

PROs:

- easy procurement of samples
- higher mode density than 1D resonators
- high repeatability of measurements
Q and frequency
- suspension point displaced easily

CONS:

- drum mode cannot be excited
- excess loss for modes rolling over the sphere

Measurements

ringdown technique [see also P. Puppo's talk]:

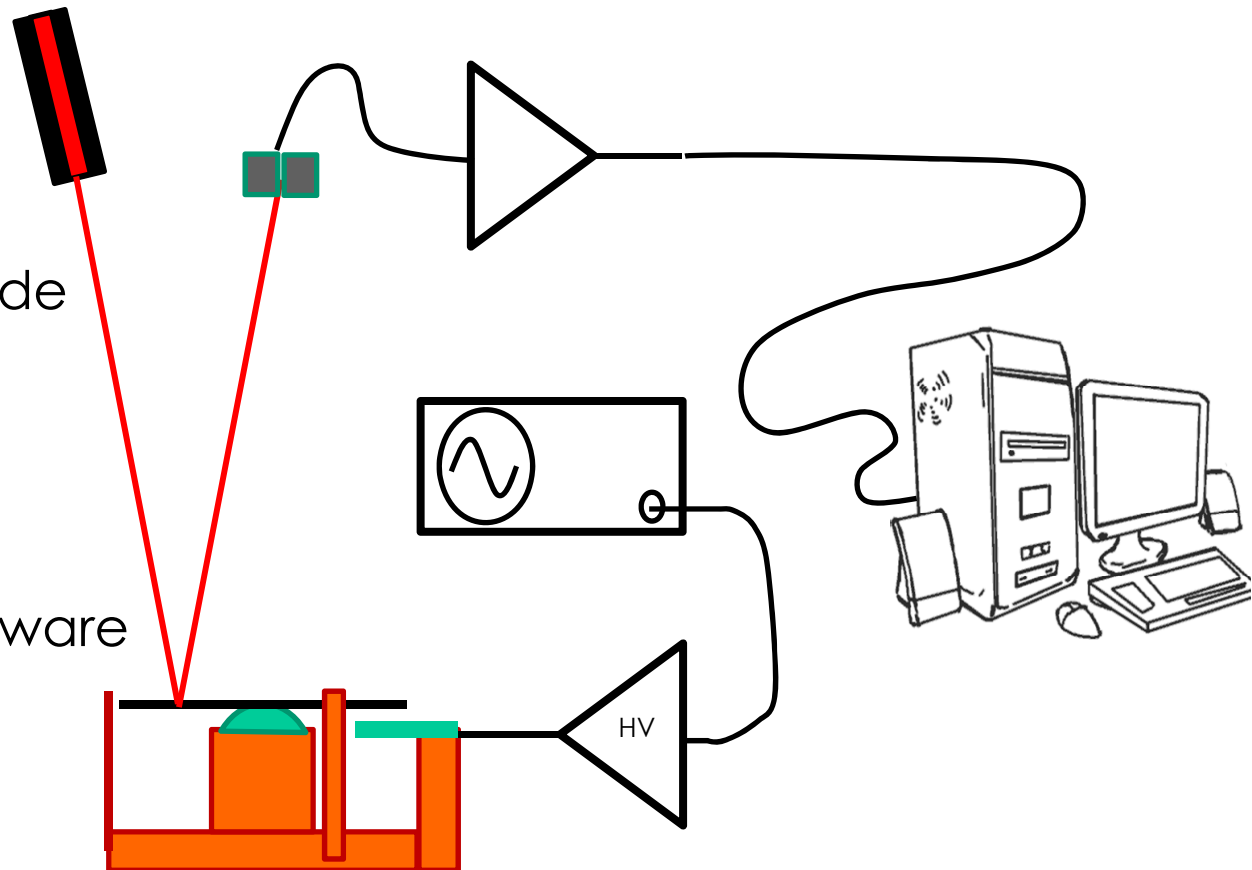
1. electrostatic excitation
2. free ringdown

vibration readout:

- optical lever
- quadrant photodiode

data acquisition:

- LabVIEW-based software

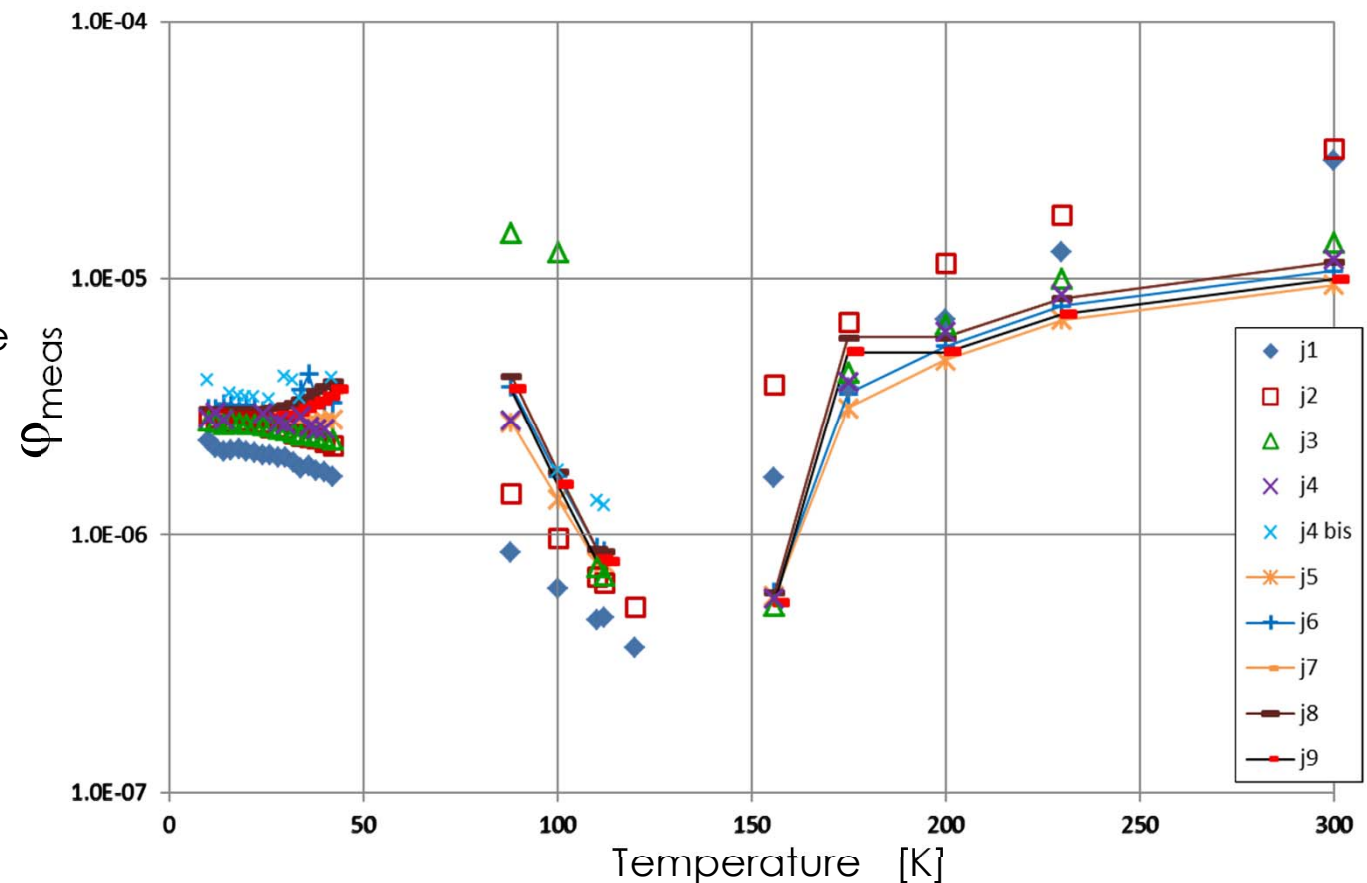


Results

raw data of sample W13006

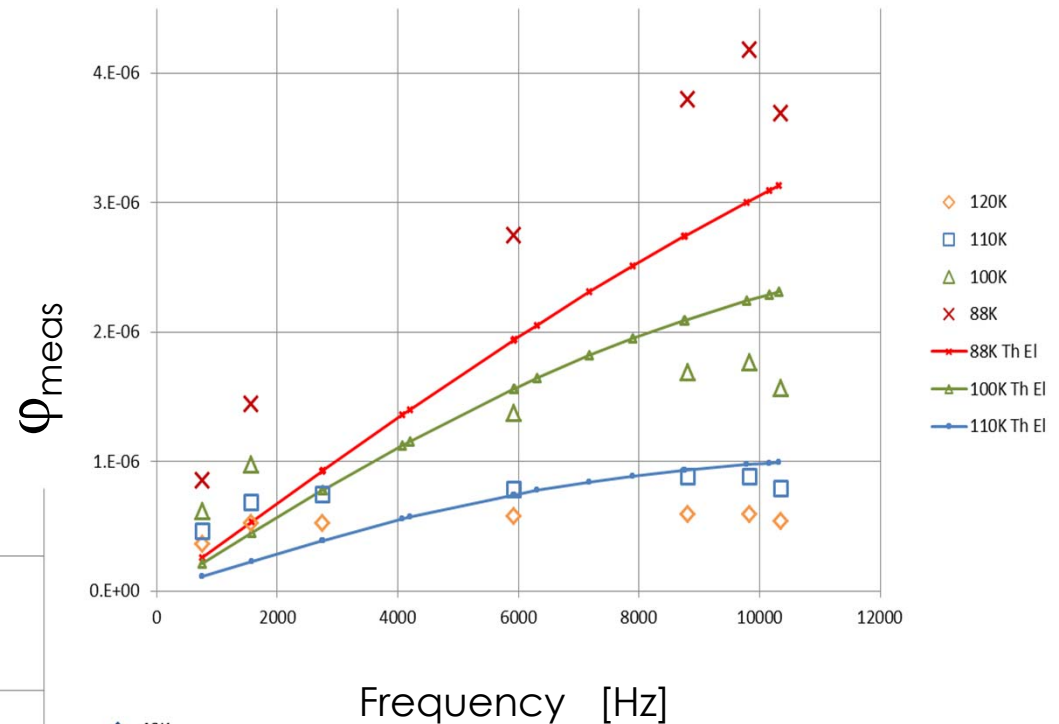
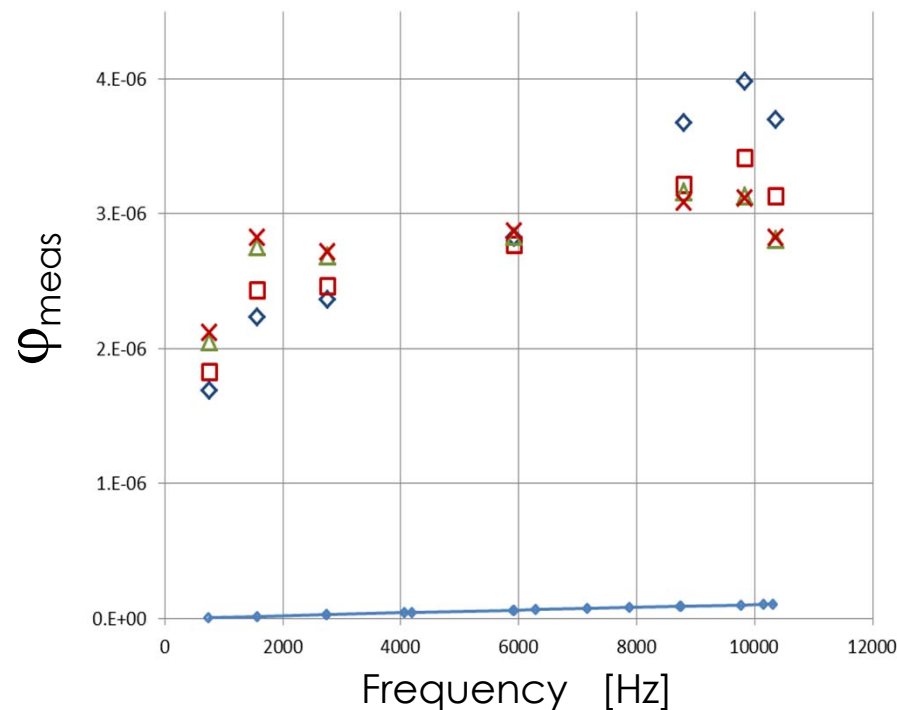
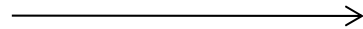
- substrate: 460 μ m-thick, 3" diameter, <100>-silicon wafer
- coating: 2.5 μ m ion-beam sputtered silica annealed at 500° C

- several modes show beating
- temperature gaps due to the L-He ended prematurely
- measured temperature is the cold plate one



Frequency dependence

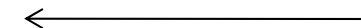
isotropic thermoelastic loss
partially explains
the measured loss



isotropic thermoelastic loss does
not explain the measured loss

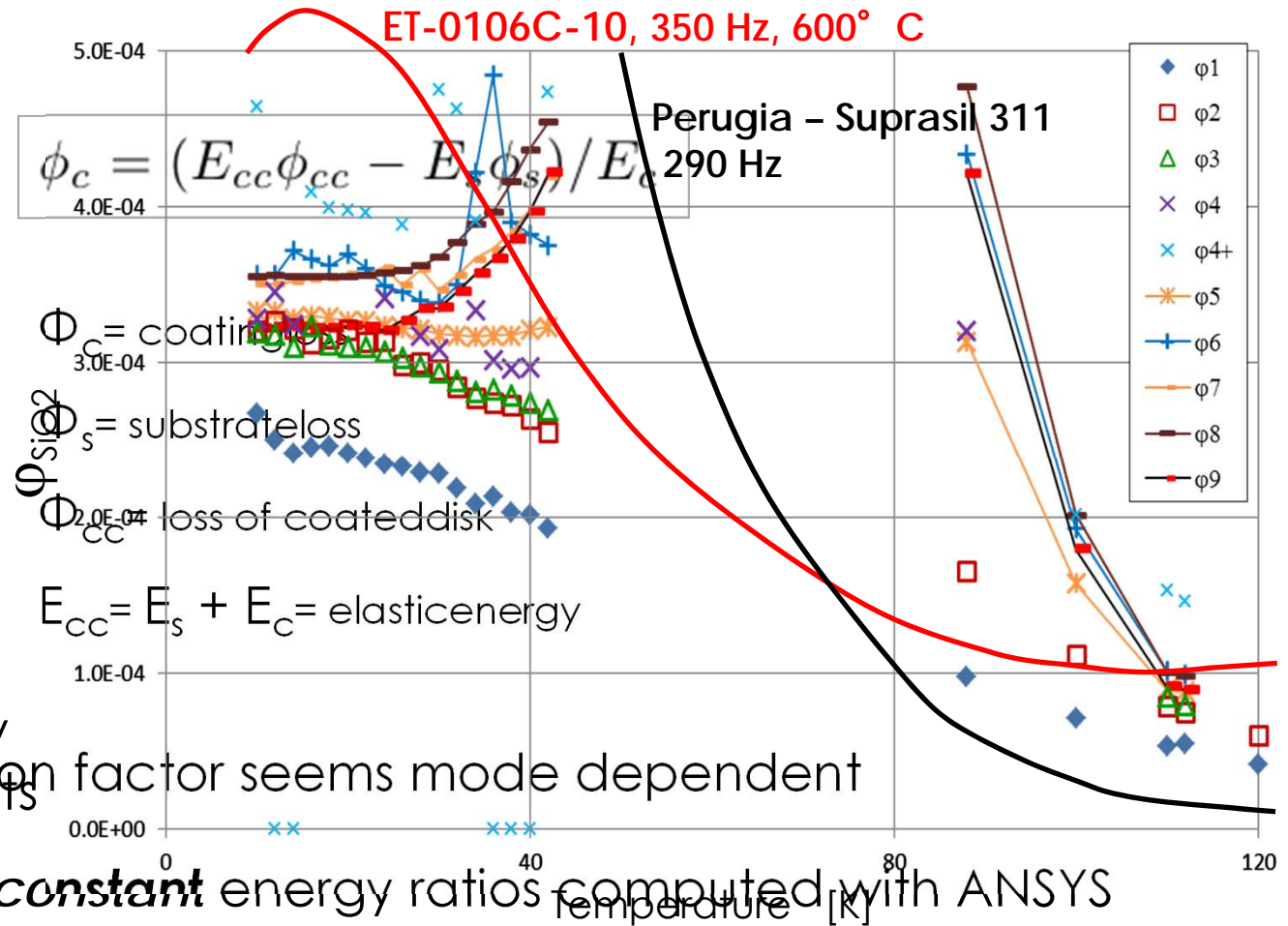
power-law behaviour below 42 K

to be confirmed by next
measurements



Coating loss

	Mode #	f [Hz]
φ1	0,2	745
φ2	0,3	1560
φ3	0,4	2740
φ4	0,5	4180
φ5	0,6	5900
φ6	0,7	7890
φ7	1,4	8770
φ8	2,2	9800
φ9	0,8	10150



Coating mechanical loss

– blades –

in collaboration with

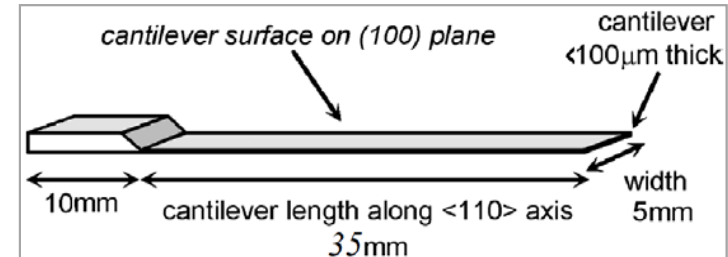
K. Craig, L. Cunningham, M. Hart, J. Hennig, J. Hough,
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Institute for Gravitational Research (IGR), University of Glasgow

Samples

Silicon blades provided by IGR:

- low-loss at low temperature
- geometry → enhance coating features

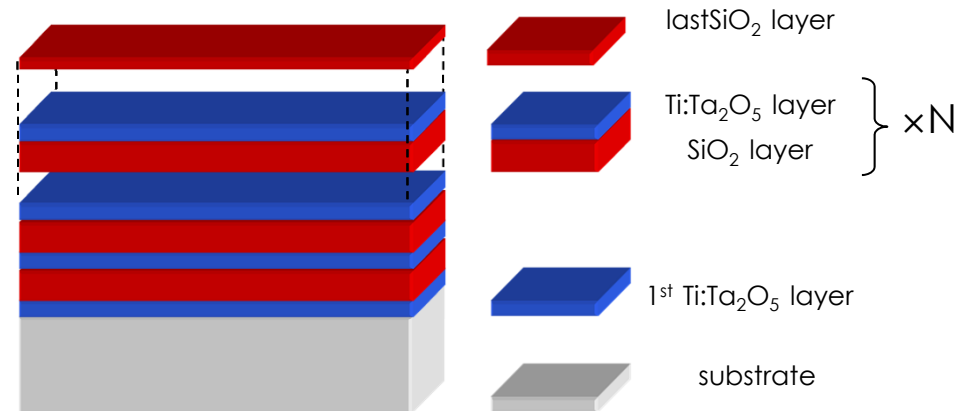


ion-beam sputtered optimized^[*] coating designed & realized by LMA for aLIGO:

- thickness = 5.9 μm (cavity end mirrors)
- $T < 5$ ppm @ 1064 nm
- optical absorption < 0.5 ppm
- low loss at room temperature

4 nominally-identical Si samples:

- 1 uncoated control blade
- 3 coated blades



+ 1 SiO₂ coated blade to cross-check room-temperature loss

[*] J. Agresti et al., SPIE Proc., 6286, 2006

Measurements

ringdown technique:

1. electrostatic excitation
2. free ringdown

vibration readout:

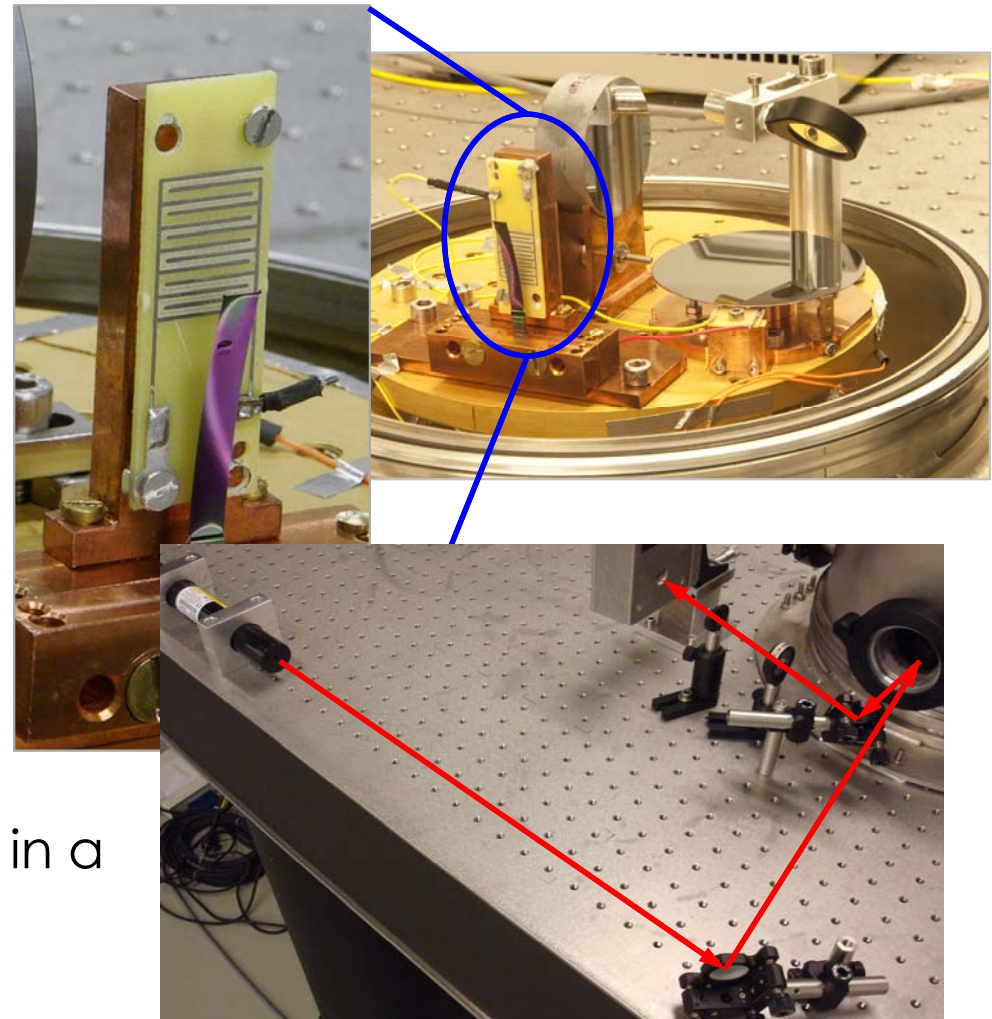
- optical lever
- position-sensitive photodiode

data acquisition:

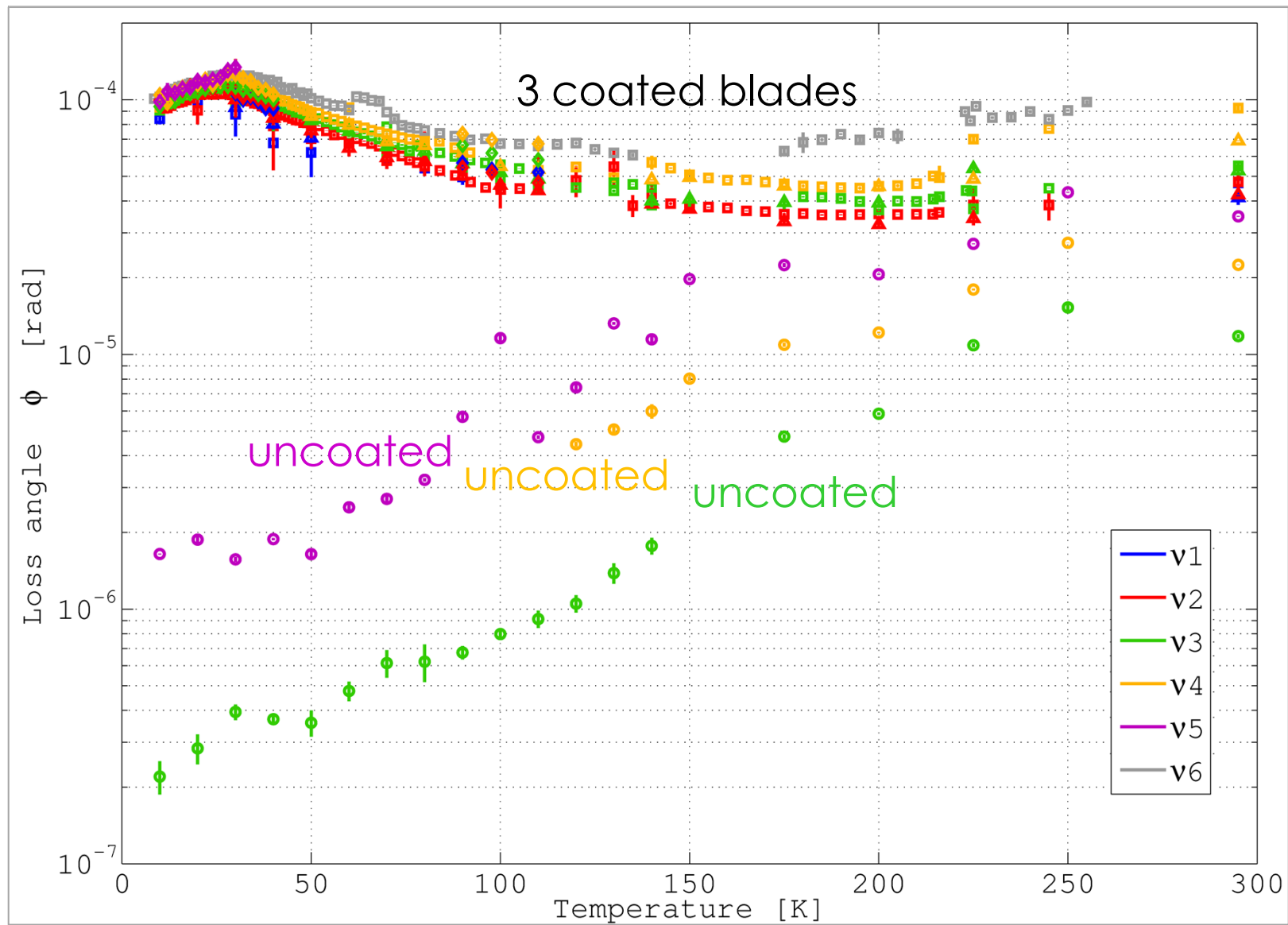
- LabVIEW-based software

same coated samples measured in a similar setup at the IGR

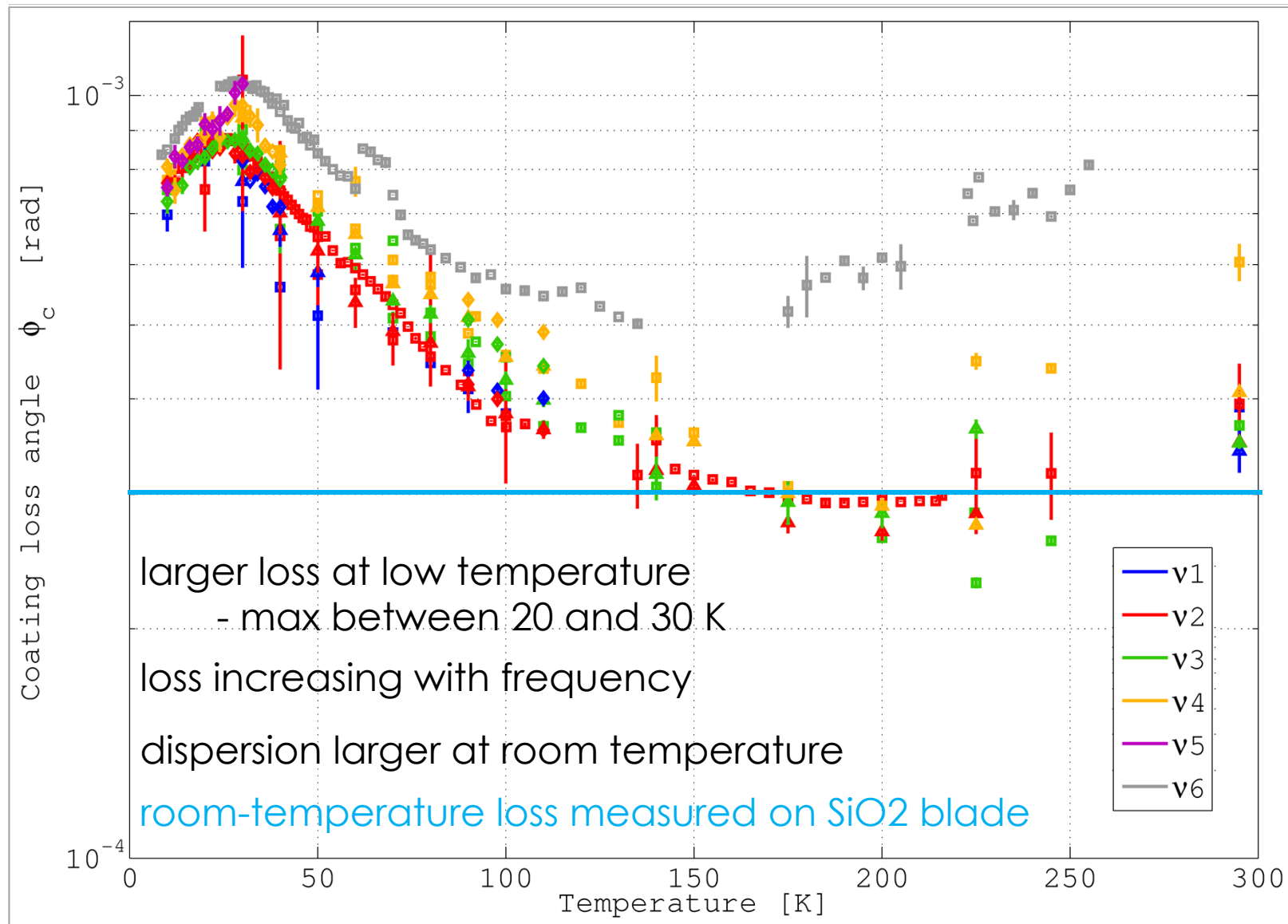
→ measurements do agree



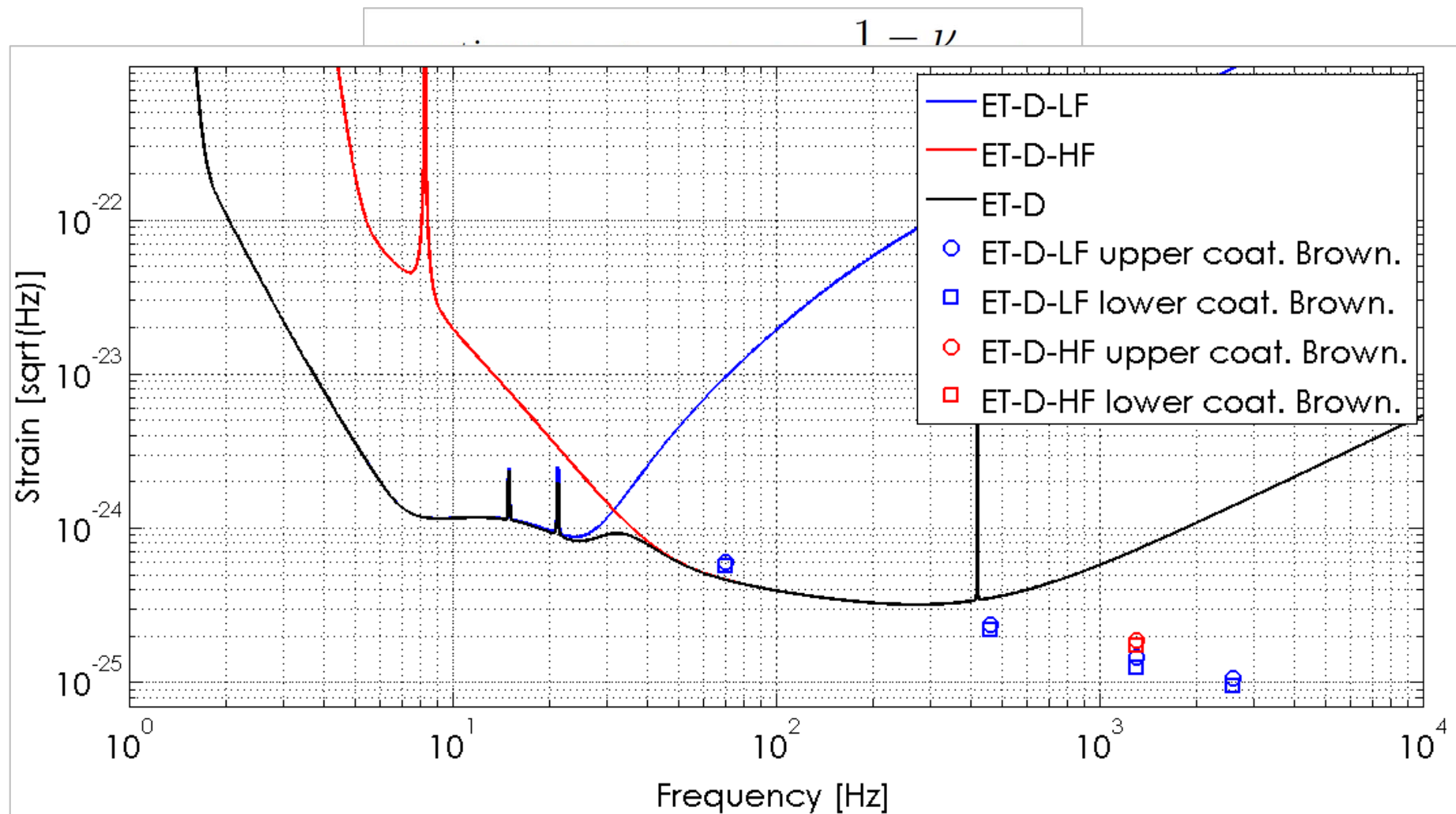
Results



Coating loss



Estimation of coating thermal noise



M. Granata & al., Einstein Telescope 4th General Meeting, Hannover 2012, ET-0019A-12

Summary and conclusions

Summary and conclusions

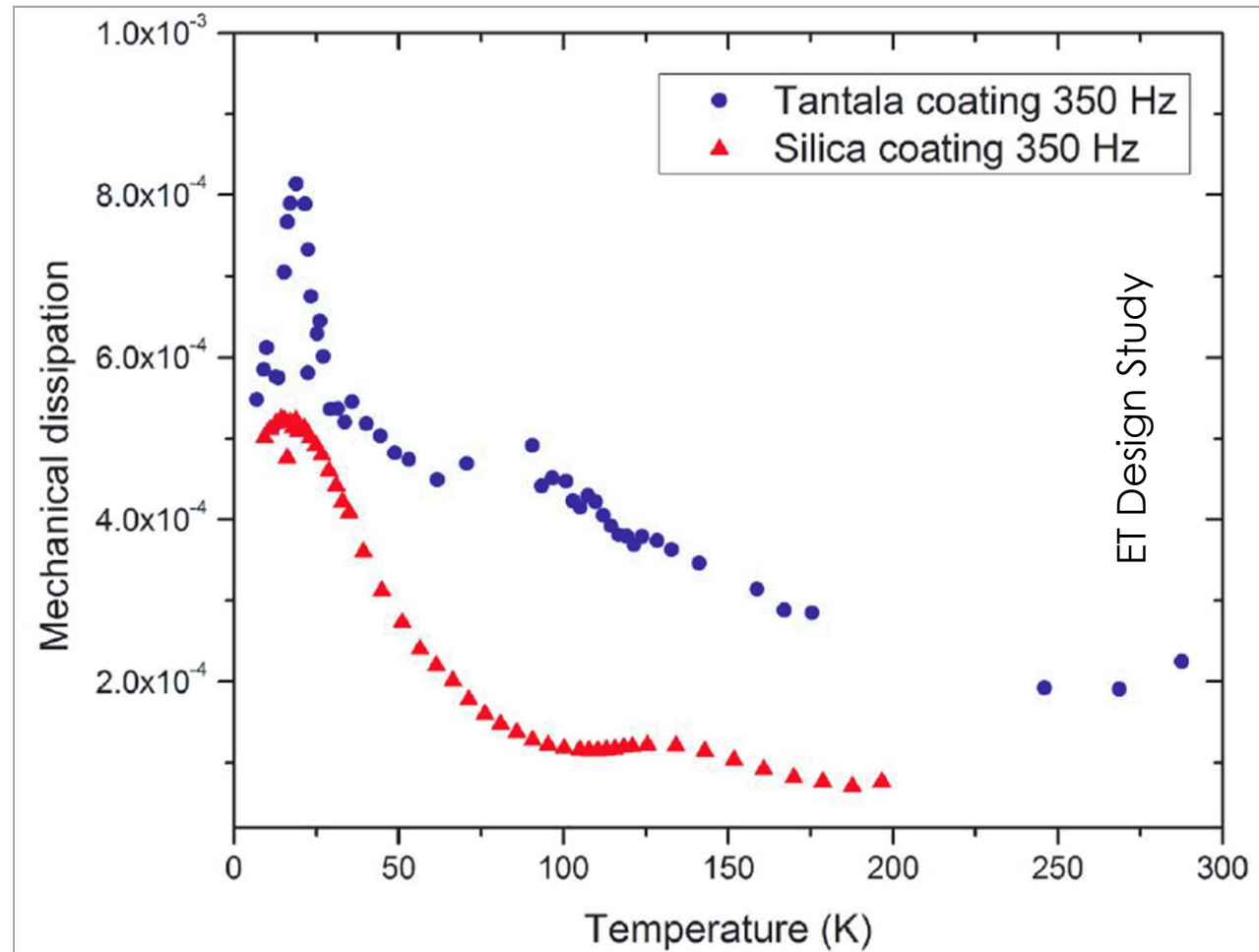
LMA is carrying out cryogenic measurements to characterize substrates and coatings at low temperature

- Si optical absorption:
 - seems not to decrease with temperature
 - to be confirmed with other samples
- coated disks: 1st cryogenic run with GeNS ever
 - anomalous behaviour of sputtered SiO₂ coating to be confirmed
 - check dilution factors and sample thermalization
- coated blades:
 - observed a low-temperature loss peak of coating stack
 - trend to be confirmed with other samples (ITM stack, ...)
 - keep improving the coating for cryogenic mirrors

Thank you for your attention

Ion-beam-sputtered fused silica

- $\Phi(T, \nu)$ for fused silica annealed @ $T_A^{AC} = 600^\circ\text{C}$, $\nu = 350$ Hz



Coatingmechanicalloss – blades –

in collaboration with

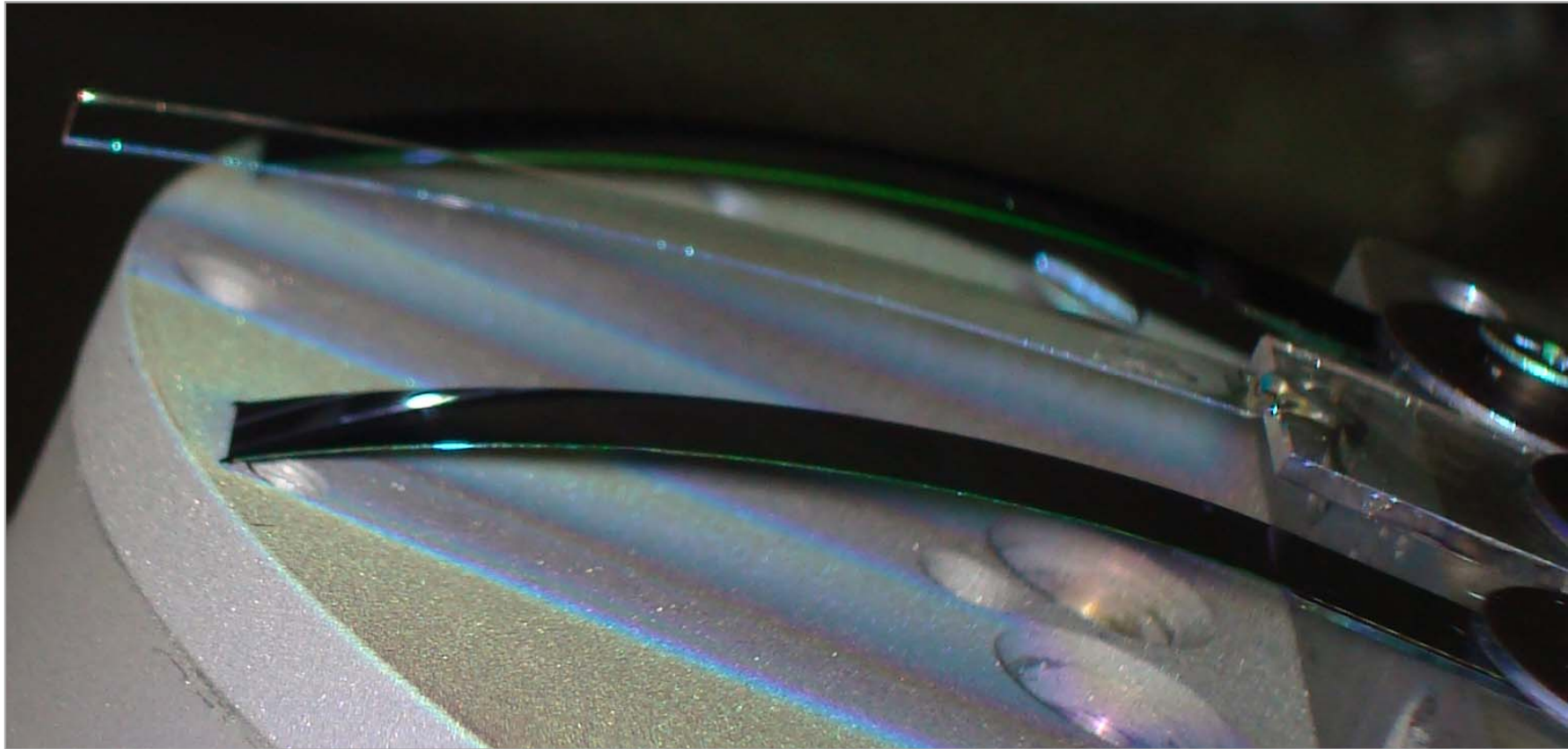
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Institute for Gravitational Research (IGR), University of Glasgow

Annealing

in-air annealing:

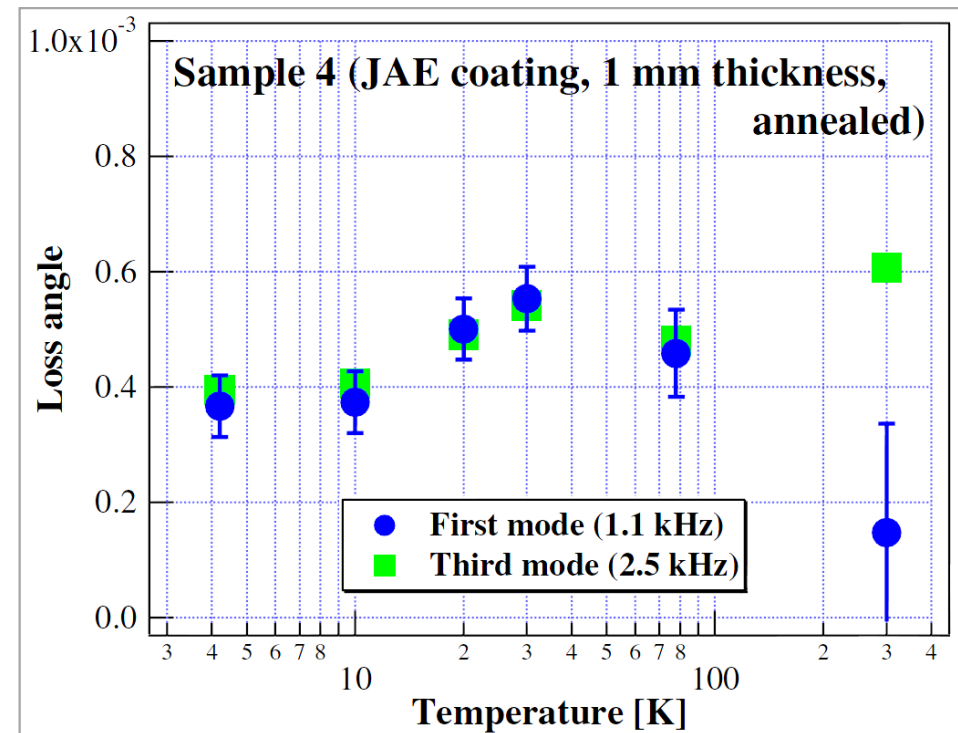
- before coating (improves bonding)
- after coating: $400^{\circ}\text{C} < T_A < 600^{\circ}\text{C}$ (decreases stresses)



Previous measurements

undoped, thinner (4.8 μm) $\text{Ta}_2\text{O}_5/\text{SiO}_2$ stack on sapphire discs

Yamamoto & al., Phys. Rev. D 74, 2006



Parameters

anisotropic multilayer coating^[*]:

1 = Ti:Ta₂O₅

2 = SiO₂

$d = d_1 + d_2 = 5.9 \text{ } \mu\text{m}$

$Y_1 = 7.32 \times 10^{10} \text{ Pa}$, $\sigma_1 = 0.17$

$Y_2 = 14.0 \times 10^{10} \text{ Pa}$, $\sigma_2 = 0.23$

for coatings @ 1064 nm, $\sigma_{\parallel} \sim 0.21$

?

measured in our setup

$$\left\{ \begin{array}{l} Y_{\perp} = \frac{d_1 + d_2}{Y_1^{-1}d_1 + Y_2^{-1}d_2} \\ Y_{\parallel} = \frac{Y_1d_1 + Y_2d_2}{d_1 + d_2} \\ \phi_{\perp} = Y_{\perp} \left(\frac{Y_1^{-1}\phi_1d_1 + Y_2^{-1}\phi_2d_2}{d_1 + d_2} \right) \\ \phi_{\parallel} = Y_{\parallel}^{-1} \left(\frac{Y_1\phi_1d_1 + Y_2\phi_2d_2}{d_1 + d_2} \right) \\ \sigma_{\perp} = \frac{\sigma_1Y_1d_1 + \sigma_2Y_2d_2}{Y_1d_1 + Y_2d_2} \\ \sigma_{\parallel} = F(Y_1, Y_2, \sigma_1, \sigma_2, d_1, d_2), \end{array} \right.$$

[*] Harry & al., CQG 19, 2002 / Harry, LIGO-T040029-00-R, 2004

Estimation of Φ_{\perp}

$$\phi_{\perp}(\phi_1, \phi_2), \phi_{\parallel}(\phi_1, \phi_2) \rightarrow \phi_{\perp}(\phi_{\parallel}, \phi_1)$$

previous equations + simple algebra:

$$\phi_{\perp}(T, \nu) = \frac{Y_{\perp}}{d} \left[\frac{\phi_{\parallel} Y_{\parallel} d}{Y_2^2} + \phi_1 d \left(\frac{1}{Y_1} - \frac{Y_1}{Y_2^2} \right) \right]$$

measured in our setup

measured by IGR
group at Glasgow

data available so far^[*]:

- $\Phi_1(T, \nu)$ for doped tantala annealed @ $T_A^{AC} = 600^{\circ}C$
- $\Phi_1(T, \nu)$ for *undoped* tantala annealed @ $T_A^{AC} = 400^{\circ}C$, $T_A^{AC} = 600^{\circ}C$

for several modes

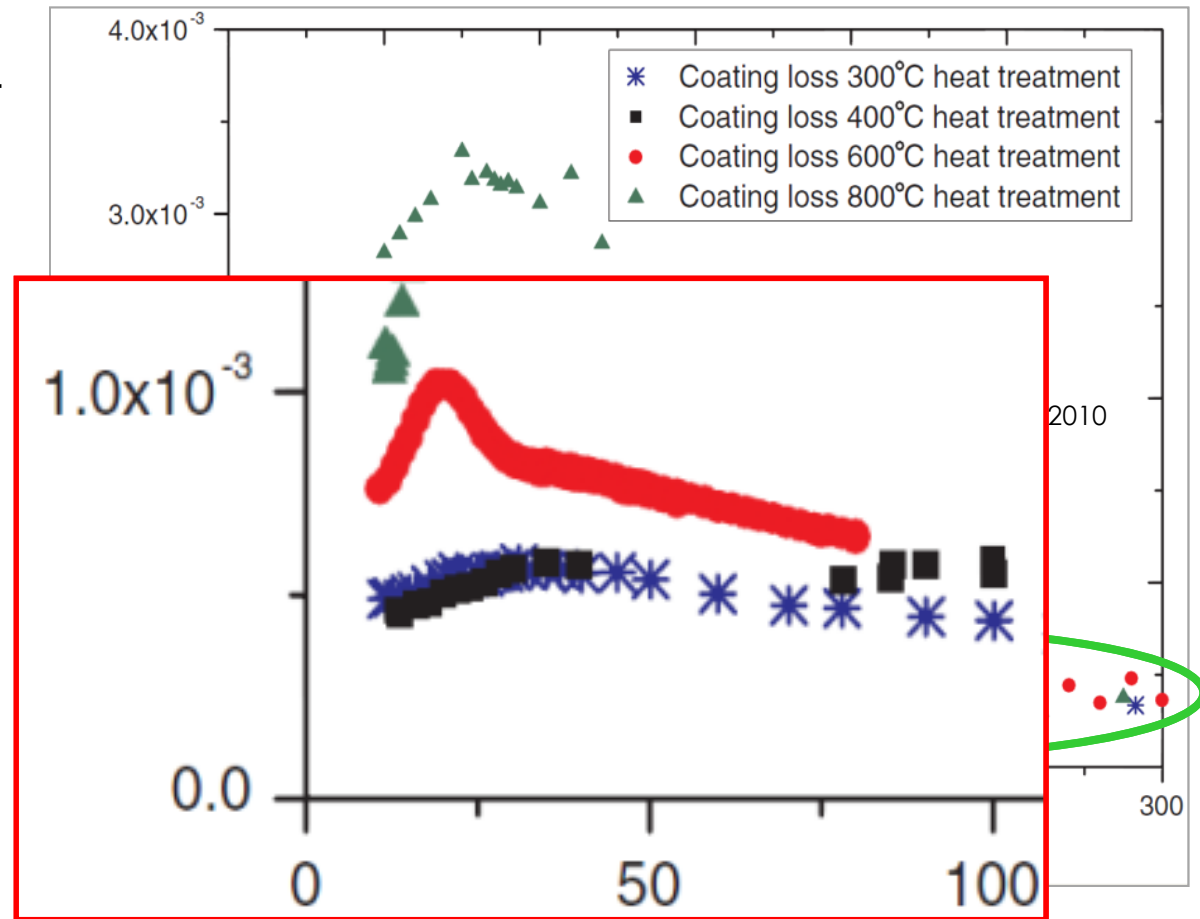
[*] I. W. Martin & al., CQG 26, 2009 / I. W. Martin & al., CQG 27, 2010

Issue

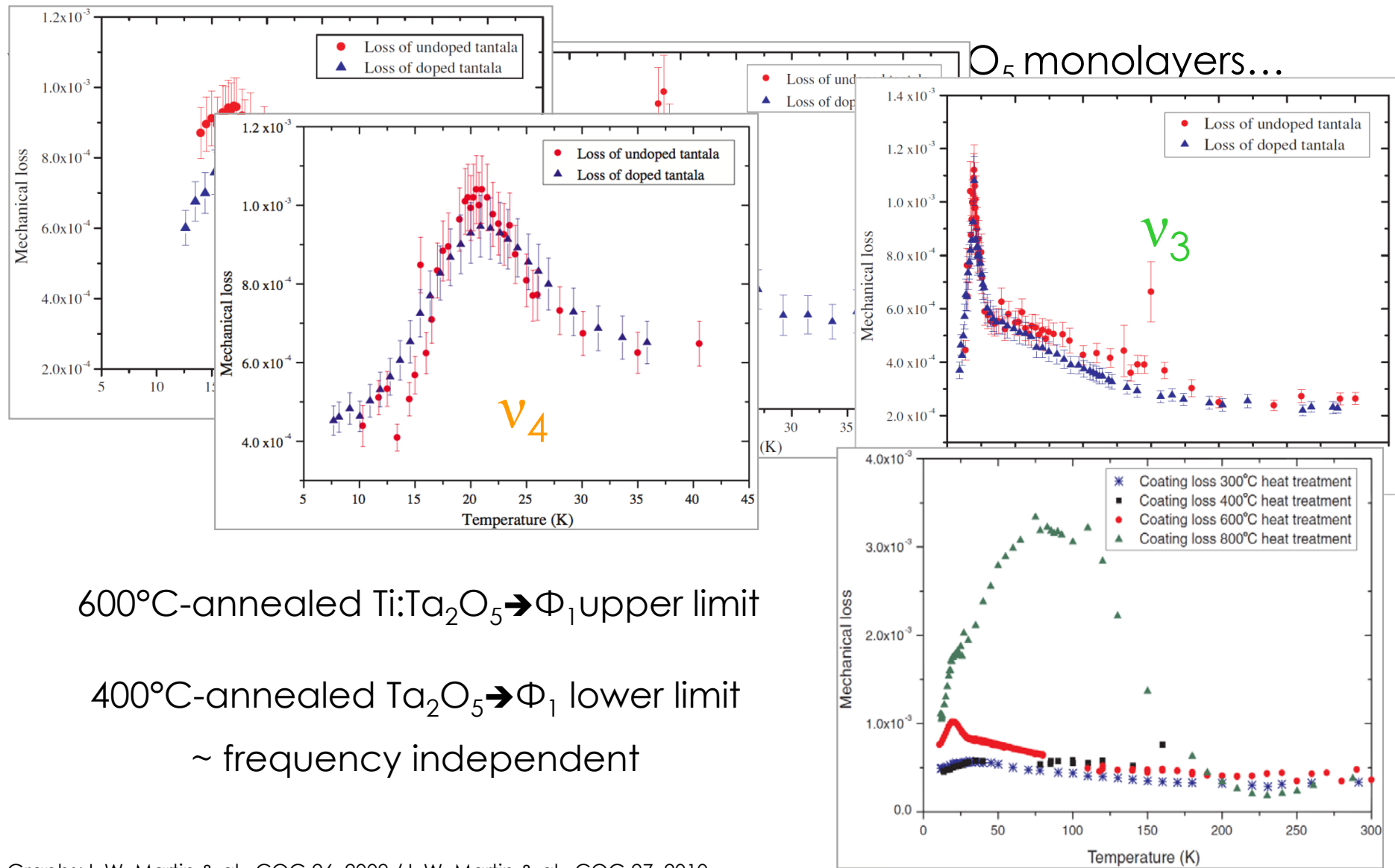
in our coating: Φ_1 annealed at 400°C ∇_A^{AC} 600°C

small difference at room T

large difference at low T



Solution



600°C-annealed $\text{Ti:Ta}_2\text{O}_5 \rightarrow \Phi_1$ upper limit

400°C-annealed $\text{Ta}_2\text{O}_5 \rightarrow \Phi_1$ lower limit

~ frequency independent

Graphs: I. W. Martin & al., CQG 26, 2009 / I. W. Martin & al., CQG 27, 2010

Estimation of coating thermal noise

anisotropic multilayer coating:

Φ_{\parallel} measured

Φ_{\perp} constrained

substrates^[*]:

SiO₂ $Y = 7.3 \times 10^{10}$ Pa, $\sigma = 0.17$

sapphire $Y = 40 \times 10^{10}$ Pa, $\sigma = 0.24$

111-Si $Y = 19 \times 10^{10}$ Pa, $\sigma = 0.22$ (!)

$$\begin{aligned} \tilde{x}^2(T, \nu) = & \frac{2k_B T}{(\pi w)^2 \nu} A_{\text{mirr}} = \frac{2k_B T}{(\pi w)^2 \nu} \frac{(1 - \sigma^2)}{Y} \frac{d}{Y_{\perp}} \\ & \times \left\{ \left[\frac{Y}{1 - \sigma^2} - \frac{2\sigma_{\perp}^2 Y Y_{\parallel}}{Y_{\perp} (1 - \sigma^2) (1 - \sigma_{\parallel})} \right] \phi_{\perp} \right. \\ & + \frac{Y_{\parallel} \sigma_{\perp} (1 - 2\sigma)}{(1 - \sigma_{\parallel}) (1 - \sigma)} (\phi_{\parallel} - \phi_{\perp}) \\ & \left. + \frac{Y_{\parallel} Y_{\perp} (1 + \sigma) (1 - 2\sigma)^2}{Y (1 - \sigma_{\parallel}^2) (1 - \sigma)} \phi_{\parallel} \right\}. \end{aligned}$$

(!) thicker coating for high reflectivity @ 1550 nm

[*] ET Design Study

Silicon substrate

shift of maximum reflectivity from $\lambda = 1064$ nm to $\lambda = 1550$ nm

→ thickness of coating increased by $a = 1550 \text{ nm} / 1064 \text{ nm} = 1.46$

$$d_{\lambda=1550 \text{ nm}} = a(d_{1\lambda=1064 \text{ nm}} + d_{2\lambda=1064 \text{ nm}}) = ad_{\lambda=1064 \text{ nm}}$$

... but stack parameters DO NOT change

$$\left\{ \begin{array}{l} Y_{\perp} = \frac{d_1 + d_2}{Y_1^{-1}d_1 + Y_2^{-1}d_2} \\ Y_{\parallel} = \frac{Y_1d_1 + Y_2d_2}{d_1 + d_2} \\ \phi_{\perp} = Y_{\perp} \left(\frac{Y_1^{-1}\phi_1d_1 + Y_2^{-1}\phi_2d_2}{d_1 + d_2} \right) \\ \phi_{\parallel} = Y_{\parallel}^{-1} \left(\frac{Y_1\phi_1d_1 + Y_2\phi_2d_2}{d_1 + d_2} \right) \\ \sigma_{\perp} = \frac{\sigma_1Y_1d_1 + \sigma_2Y_2d_2}{Y_1d_1 + Y_2d_2} \\ \sigma_{\parallel} = F(Y_1, Y_2, \sigma_1, \sigma_2, d_1, d_2), \end{array} \right.$$